

What is claimed is:

1. A photocatalytic member comprising:
a substrate;
an undercoat layer formed on a surface of said substrate; and
a photocatalyst layer formed on a surface of said undercoat layer,
wherein the main component of said undercoat layer is a crystalline zirconium compound, said photocatalyst layer is constituted of a crystalline phase, and said substrate has a low heat resistant element.
2. The photocatalytic member according to claim 1, wherein said crystalline zirconium compound includes monoclinic zirconium oxide crystals.
3. The photocatalytic member according to claim 1 or 2, wherein said substrate is comprised of low heat resistant glass.
4. The photocatalytic member according to claim 1 or 2, wherein said substrate is a resin substrate.
5. The photocatalytic member according to claim 1 or 2, wherein said substrate is a resin film.
6. The photocatalytic member according to claim 1 or 2, wherein said substrate is an organic-inorganic composite substrate.
7. The photocatalytic member according to claim 1 or 2, wherein said substrate is comprised of low heat resistant metal.

8. The photocatalytic member according to any one of claims 1 to 7, wherein said substrate includes a non-heat-resistant thin film.
9. The photocatalytic member according to claim 8, wherein said non-heat-resistant thin film is a heat ray reflecting film in which silver is used.
10. The photocatalytic member according to claim 9, wherein said non-heat-resistant thin film is a heat ray reflecting film in which a laminated film of dielectric layer/silver layer/dielectric layer is used.
11. The photocatalytic member according to claim 9, wherein said non-heat-resistant thin film is a heat ray reflecting film in which a laminated film of dielectric layer/silver layer/dielectric layer/silver layer/dielectric layer is used.
12. The photocatalytic member according to any one of claims 1 to 11, wherein said substrate has a heat resistance temperature of 700°C or below.
13. The photocatalytic member according to any one of claims 1 to 11, wherein said substrate has a heat resistance temperature of 500°C or below.
14. The photocatalytic member according to any one of claims 1 to 13, wherein the main component of said photocatalyst layer is a titanium compound.
15. The photocatalytic member according to claim 14, wherein said titanium compound is tetragonal titanium oxide.

16. The photocatalytic member according to claim 14 or 15, wherein said titanium compound is anatase type titanium oxide.
17. The photocatalytic member according to any one of claims 1 to 16, wherein said non-heat-resistant thin film, said undercoat layer and said photocatalyst layer are formed by a vapor phase method.
18. The photocatalytic member according to claim 17, wherein said vapor phase method is a sputtering method.